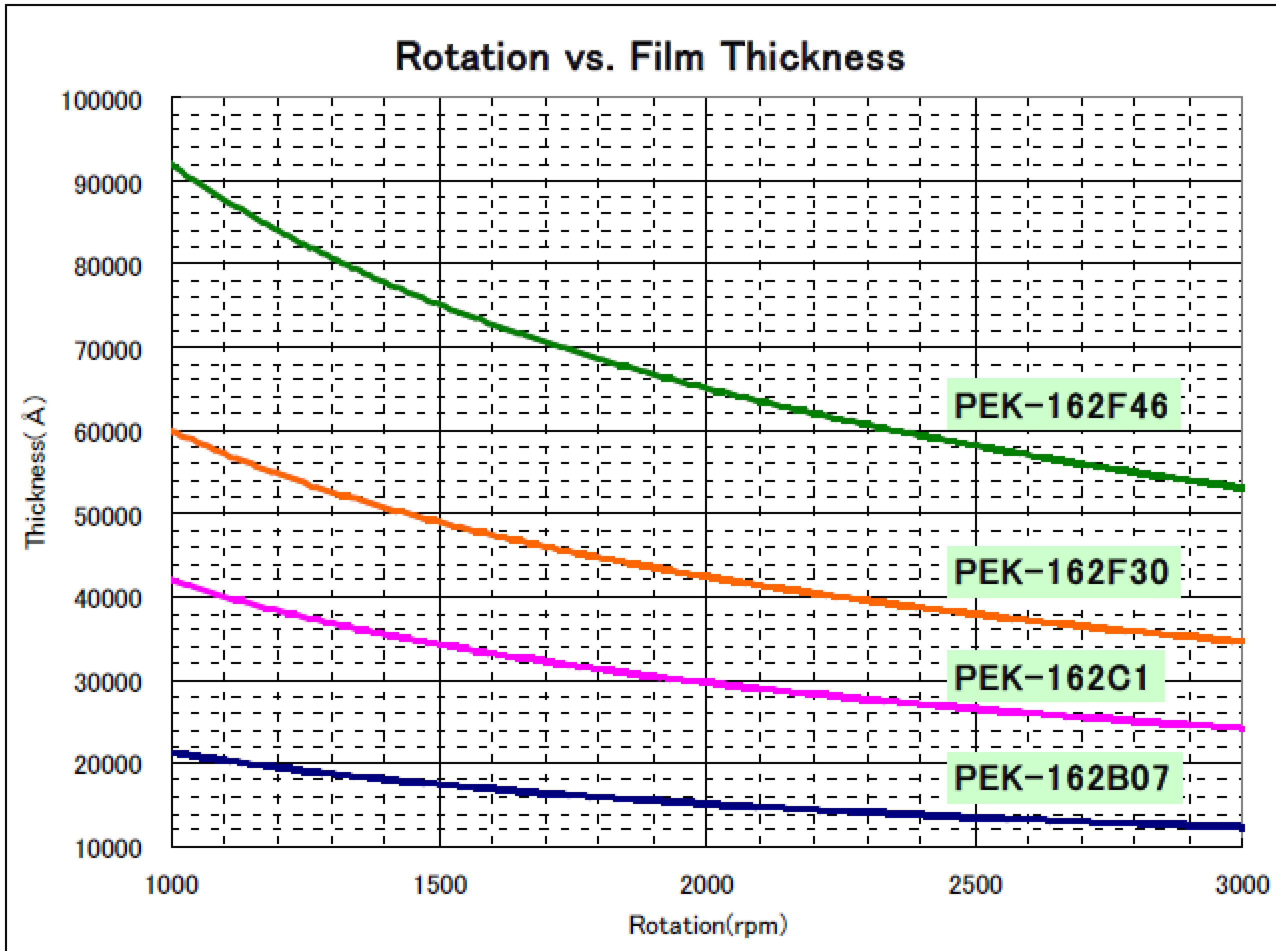
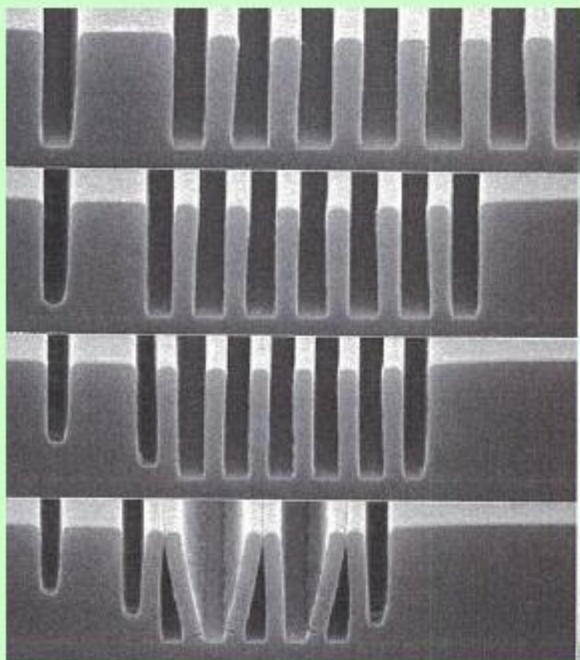
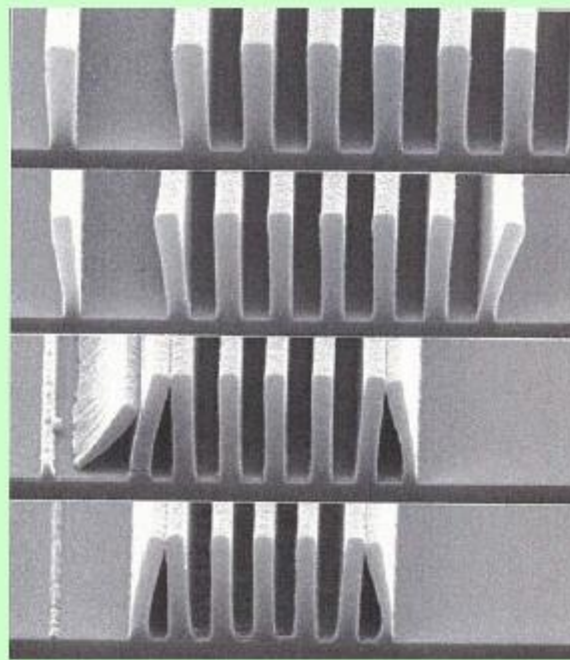



We carry PEK-162C1

**Substrate:** Bare-Si
**RESIST Film Thickness:** 2.0um / 3.0um
**Bake:** **SB** 100C60s/**PEB** 90C60s
**TARC;** AQUATARⅧ (90°C/60sec FT430Å)
**Exposure:** Nikon NSR-2005EX12B NA0.55, σ0.8 conv.
**Photomask:** Binary
**Dev.:** TMAH 2.38%, w/o surfactant, 23C
60s puddle (FT2.0um) / 30s+60s puddle (FT3.0um)

For our lab, use AZ300MIF developer (0.26N, not 0.24N)
We do not carry Aquatar TARC, Use AR2 for underlayer.
Develop 60s puddle, gentle agitation.

# PEK-162 pattern profile and Resolution data F.T. 2.0um

| Dark FIELD 28.5mJ/cm2 | Mask size | Bright FIELD 27mJ/cm2 |
|---|---|---|
|  | 500nmL/S<br>400nmL/S<br>375nmL/S<br>350nmL/S |  |

## PEK-162 pattern profile and Resolution data F.T. 3.0um